

Introduction

- Elemental analysis of process chemicals at ultra-trace levels (ng/L; ppt) is a vital application to ensure the yield and operational reliability of semiconductor devices.
- Isopropyl alcohol (IPA) is used to remove organic and metallic residues and impurities from the surface of silicon wafers.
- Since IPA comes into direct contact with the wafer surface, it is necessary to control the concentration of trace metals present in the organic solvent.
- SEMI standard C41-0705 specifies a maximum contaminant level of less than 100 ppt for each element in high purity grade 4 IPA [1].
- Advanced analytical skills are required for the application.

In this study, impurities in IPA were quantified by Method of Standard Addition (MSA) using an Automatic Standard Addition System (ASAS) (IAS Inc. Japan) and triple quadrupole ICP-MS (ICP-MS/MS). The method allows the quantification of ultra-trace level impurities in IPA regardless of the skill level of the analyst.

Experimental

Reagents and samples

- Sample: distilled IPA (Electronic Grade).
- Standard stock solution for MSA: a 1 µg/L (ppb) mixed multi-element standard solution was prepared by diluting a 10 ppm mixed multi-element standard solution: XSTC-7, XSTC-8 and XSTC-331 (SPEX CertiPrep, NJ, US) with distilled IPA. Nitric acid (68% ultrapure HNO₃ (TAMAPURE-AA-10)) was added to 1% to stabilize the spiked elements in the IPA sample.
- The stock solution was loaded on the ASAS.
- All target concentration solutions required for the analysis were automatically prepared by the ASAS.
- All preparation and analysis steps were performed in a Class 10,000 clean room.

Instrumentation

- Standard Agilent 8900 Semiconductor configuration ICP-MS/MS instrument with s-lens equipped with:
 - A glass coaxial nebulizer.
 - Peltier cooled quartz spray chamber
 - Quartz torch (1.5 mm id)
 - Platinum-tipped sampling and skimmer cones

Tuning conditions are shown in Table 1, other acquisition parameters are shown in Table 2. A photo of the ASAS fitted to the ICP-MS/MS is shown in Figure 1.

Table 1. ICP-MS/MS operating conditions.

	H ₂ (MG0.8)	NH ₃	No gas	H ₂ (MG0.5)	He	O ₂ He
Scan type	MS/MS					
RF power (W)	1500					
Sampling depth (mm)	18					
Carrier gas flow rate (L/min)	0.70					
20% O ₂ Ar balance gas flow rate (L/min)	0.30 (30 % of full scale)					
Spray chamber temp (°C)	-5					
Makeup gas (MG) flow rate (L/min)	0.80	0.70	0.50			
He gas flow rate (mL/min)	-	1	-	-	5	12
H ₂ gas flow rate (mL/min)	5	-	-	10	-	-
NH ₃ gas flow rate (mL/min)	-	2.0 (20%)	-	-	-	-
O ₂ gas flow rate (mL/min)	-	-	-	-	-	0.075 (5%)
OctP bias (V)	-18	-5	-10	-30	-20	-3
Axial acceleration (V)	1	0				1
Energy discrimination (V)	0	-10	3	-10	3	-10

Table 2. Acquisition parameters.

Parameter	Setting
Q2 peak pattern	1 point
Replicates	3 (spiked solution) 10 (unspiked solution)
Sweeps/replicate	10
Integration time	Phosphorus: 10 sec, all other elements: 1 sec



Figure 1. ASAS-ICP-MS/MS.

Experimental

Automated Standard Addition System (ASAS)

The operation of the IAS Automated Standard Addition System (ASAS) is described in the working example and in Figure 2.

Working example: How to add a 50 ppt spike to the sample?

- Prepare a 1 ppb standard stock solution for MSA.
 - When the autosampler probe moves to one of the vials, it triggers the automatic measurement of the sample uptake rate using two flow sensors.
 - An air bubble is introduced from the valve labeled "Air Valve".
 - Optical fiber sensors then measure the time it takes for the air bubble to pass from Sensor 1 to Sensor 2. (The flow rate will be approximately 200 µL/min in self-aspiration mode).
 - The ASAS software automatically calculates the flow rate of the 1 ppb stock standard required to achieve the 50 ppt spike level.
 - The standard will be introduced to the sample via the "Mix Block" at the calculated flow rate by the syringe pump.
- In this example, introducing a 1 ppb stock standard solution at 10.0 µL/min would equate to spiking the sample at the 50 ppt concentration level.
- The syringe pump delivers the standard solution from the loop into the sample line via the "Mix Block". The appropriate flow rate is calculated automatically, as explained in the working example. The MSA solution is then introduced into the plasma of the ICP-MS using a nebulizer operating in self-aspiration mode.

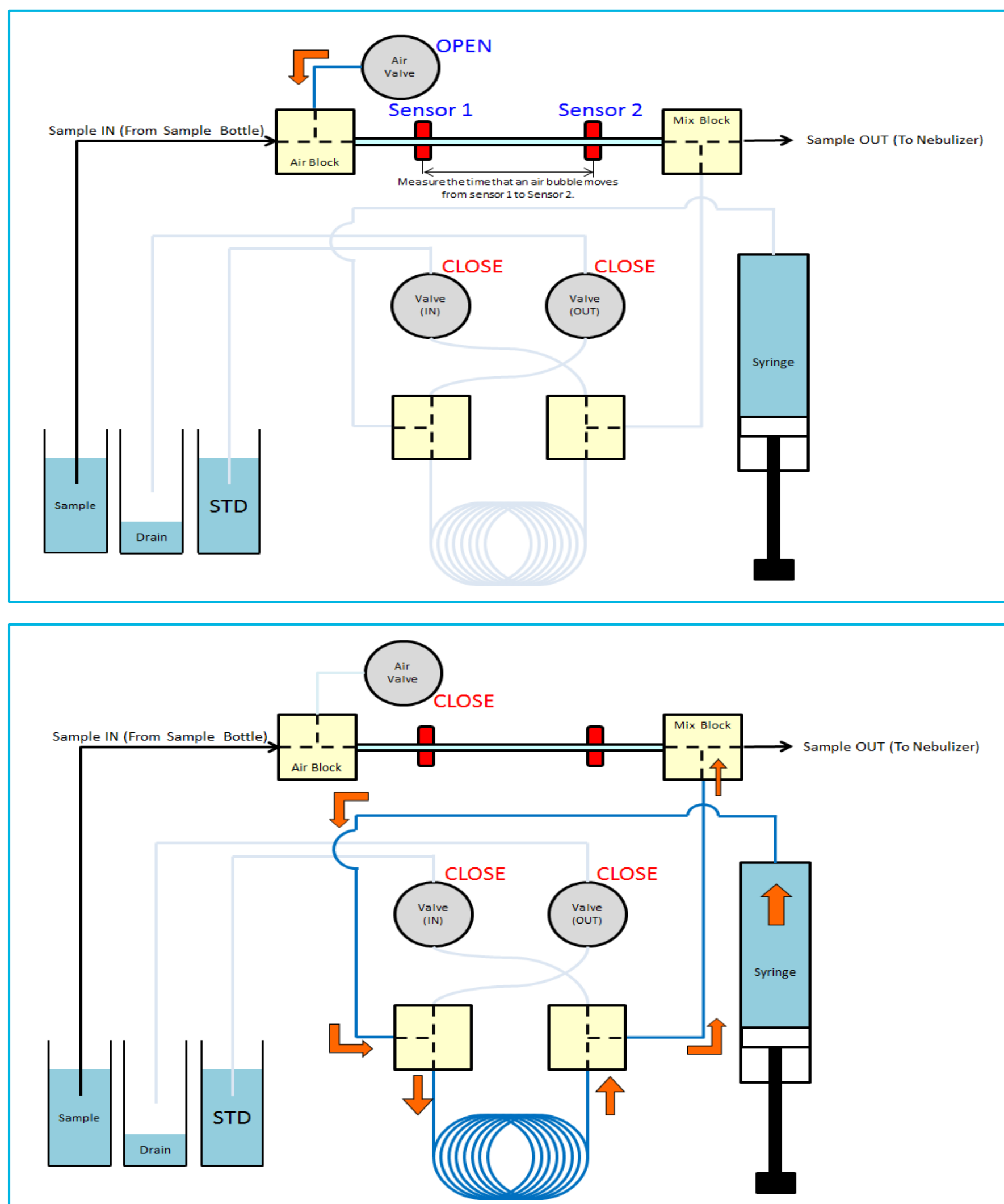


Figure 2. Operation of the ASAS.

Results and Discussion

DLs and BECs

- 48 elements were measured in IPA using the 8900 operating in multiple tune modes.
- Quantitative results and DLs for SEMI and non-SEMI specified elements are shown in Table 4.
- Each detection limit was calculated as 3-sigma of 10 replicate measurements of a blank IPA sample.

Mg, Al, and Cr determination

Combining cool plasma with CRC technology is a powerful mode for interference removal [2].

In this study, a more robust warm plasma was used and a small amount of oxygen gas was mixed with argon gas to decompose the carbon matrix thus avoiding carbon deposition on the interface cones.

Because the major isotope of ²⁴Mg⁺ suffers an interference from ¹²Cr¹²C⁺ in organic samples, Mg was determined using a warm plasma with NH₃ cell gas.

- The calibration curve for ²⁴Mg shows that ¹²Cr¹²C⁺ interference was removed successfully.
- BEC for Mg: 0.082 ng/L (ppt).
- DL for Mg: 0.020 ppt (Table 3).

The same approach was effective for the determination of other interfered elements such as ²⁷Al and ⁵²Cr.

P determination

In this study, the same measurement conditions proposed by Mizobuchi et al were used for P (He+O₂ mode) [4].

- The calibration curve in Figure 3 shows good linearity from 5 to 50 ppt for P.
- BEC for P: 43 ng/L (ppt).
- DL for P: 2.6 ppt (Table 3).

Table 3. Main interferences in organic solvents.

Analyte	Interferences	DL (ng/L)	BEC (ng/L)
²⁴ Mg	¹² Cr ¹² C ⁺	0.020	0.082
²⁷ Al	¹² C ¹⁵ N ⁺ , ¹³ C ¹⁴ N ⁺ , ¹² C ¹⁴ N ¹ H ⁺ [3]	0.042	0.16
⁵² Cr	⁴⁰ Ar ¹² C ⁺	0.16	0.48
³¹ P	¹⁵ N ¹⁶ O ⁺ , ¹⁴ N ¹⁷ O ⁺ , ¹³ C ¹⁸ O ⁺	2.6	43

Results and Discussion

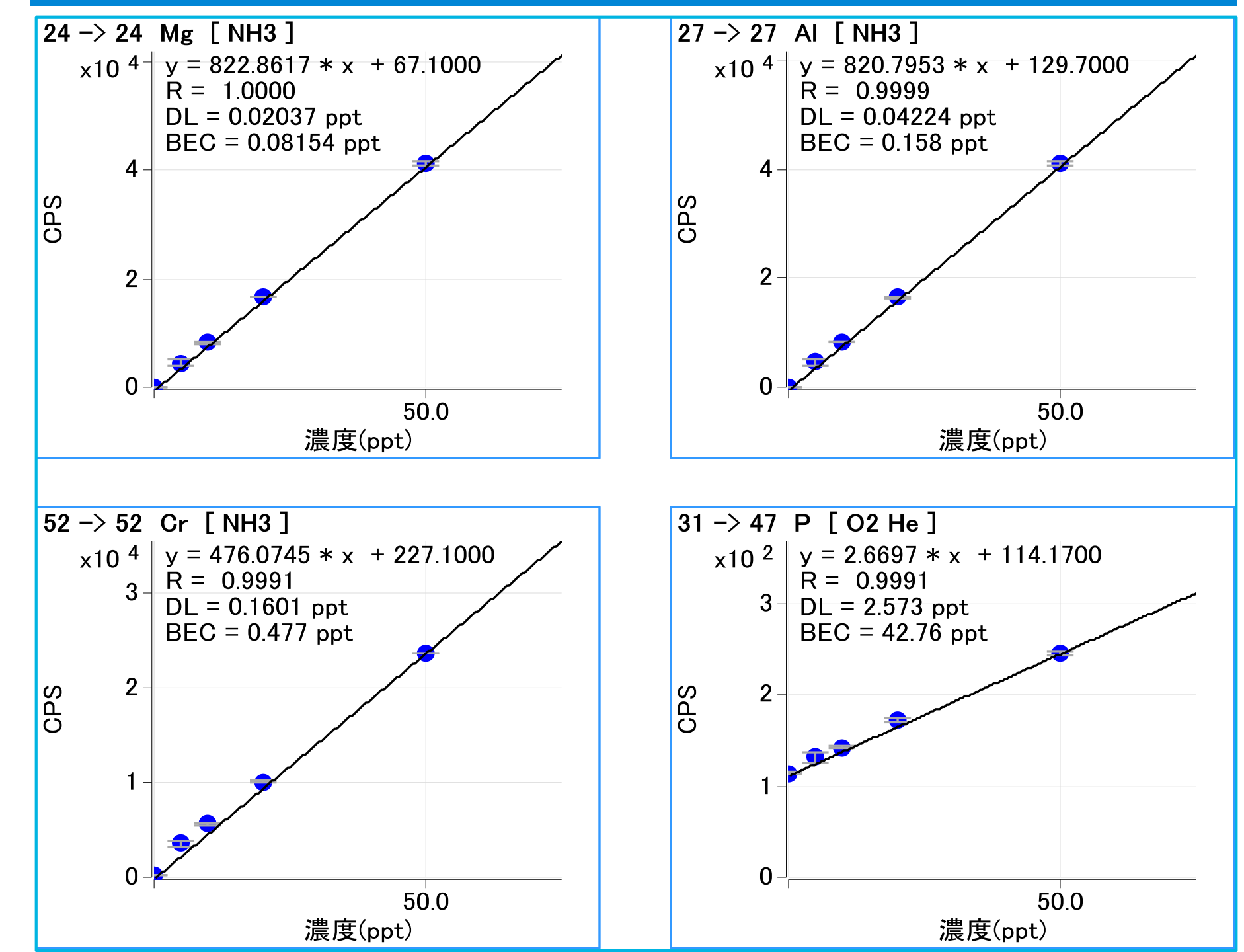


Figure 3. MSA calibration curves for ²⁴Mg, ²⁷Al, ⁵²Cr, ³¹P.

Table 4. DLs and BECs in IPA. Analytes shown in bold are SEMI grade 4 elements.

Analyte	Q1	Q2	Tune Mode	DL (ng/L)	BEC (ng/L)	20 ng/L Recovery(%)
Li	7	7	H ₂ (MG0.8)	0.010	0.040	99
Be	9	9	No gas	0.023	0.005	99
B	11	11	No gas	1.2	12	96
Na	23	23	NH ₃	0.060	0.97	109
Mg	24	24	NH ₃	0.020	0.082	102
Al	27	27	NH ₃	0.042	0.16	100
P	31	47	O ₂ He	2.6	43	99
K	39	39	NH ₃	1.6	2.7	107
Ca	40	40	NH ₃	0.19	0.62	108
Ti	48	64	O ₂ He	0.23	1.3	99
V	51	67	O ₂ He	0.020	0.030	99
Cr	52	52	NH ₃	0.16	0.48	92
Mn	55	55	NH ₃	0.030	0.030	102
Fe	56	56	NH ₃	0.16	1.1	101
Co	59	59	He	0.020	0.020	99
Ni	60	60	He	0.43	0.80	101
Cu	63	63	O ₂ He	0.38	6.4	97
Zn	64	64	He	0.71	0.72	98
Ga	71	71	O ₂ He	0.013	0.005	100
Ge	74	74	He	0.30	0.070	96
As	75	91	O ₂ He	0.41	0.26	108
Sr	88	88	O ₂ He	0.005	0.002	98
Zr	90	106	O ₂ He	0.030	0.020	99
Nb	93	93	H ₂ (MG0.5)	0.14	0.41	102
Mo	98	130	O ₂ He	0.17	0.11	103
Ru	101	101	He	0.080	0.03	99
Rh	103	103	O ₂ He	0.070	0.18	99
Pd	105	105	O ₂ He	0.070	0.040	100
Ag	107	107	O ₂ He	0.014	0.006	97
Cd	111	111	O ₂ He	0.035	0.004	98
In	115	115	O ₂ He	0.012	0.008	99
Sn	118	118	O ₂ He	0.058	0.034	100
Sb	121	121	O ₂ He	0.056	0.009	103
Te	125	125	O ₂ He	0.78	0.29	97
Cs	133	133	H ₂ (MG0.8)	0.060	0.022	96
Ba	138	138	O ₂ He	0.009	0.004	99
Hf	178	178	He	0.000	0.000	105
Ta	181	213	O ₂ He	0.033	0.009	96
W	182	214	O ₂ He	0.21	0.049	97
Re	185	185	O ₂ He	0.000	0.000	96
Ir	193	193	No gas	0.060	0.006	101
Pt	195	195	O ₂ He	0.51	0.45	100
Au	197	197	O ₂ He	0.063	0.007	110
Tl	205	205	O ₂ He	0.029	0.015	99
Pb	208	208	O ₂ He	0.047	0.042	100
Bi	209	209	O ₂ He	0.021	0.004	98
Th	232	248	O ₂ He	0.11	0.022	97
U	238	254	O ₂ He	0.18	0.048	91

Conclusions

- By providing a high degree of automation, the Agilent 8900 ICPMS/MS fitted with IAS's ASAS auto-MSA system simplifies the elemental analysis of semiconductor process chemicals.
- Eliminating manual tasks during ultratrace analysis lowers the risk of contamination. Limiting the handling of reagents and samples also reduces the likelihood of errors arising during the experimental procedure, leading to an increased confidence in the data quality.
- The elements specified in SEMI C41-0705, including P were measured at sub-ppt to ppt levels in IPA. The results exceed current SEMI specifications for IPA.

References

- SEMI C41-0705, Specifications and Guidelines for 2-Propanol (2005).
- J. Takahashi and K. Mizobuchi, Asia Pacific Winter Conference on Plasma Spectroscopy, 2008
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